



# Optical Technology and Measurement for Industrial Applications Conference

(OPTM 2020)

*Program Committee:* **Masato Aketagawa**, Nagaoka Univ. of Technology (Japan); **Yasuhiro Arai**, Kansai Univ. (Japan); **Prathan Buranasiri**, King Mongkut's Institute of Technology Ladkrabang (Thailand); **Jürgen W. Czarske**, TU Dresden (Germany); **Motoharu Fujigaki**, Univ. of Fukui (Japan); **Amalia Martínez-García**, Centro de Investigaciones en Óptica, A.C. (Mexico); **Satoshi Gonda**, National Institute of Advanced Industrial Science and Technology (Japan); **Sen Han**, Univ. of Shanghai for Science and Technology (China); **Feng-Lei Hong**, Yokohama National Univ. (Japan); **Nathan Hagen**, Utsunomiya Univ. (Japan); **Hideki Ina**, Canon Inc. (Japan); **Ichiro Ishimaru**, Kagawa Univ. (Japan); **Lianhua Jin**, Univ. of Yamanashi (Japan); **Daesuk Kim**, Chonbuk National Univ. (Korea, Republic of); **Jonathan D. Kofman**, Univ. of Waterloo (Canada); **Kazuhide Kamiya**, Toyama Prefectural Univ. (Japan); **Qian Kemao**, Nanyang Technological Univ. (Singapore); **Fumio Koyama**, Tokyo Institute of Technology (Japan); **Ryoichi Kuwano**, Hiroshima Institute of Technology (Japan); **Yu-Lung Lo**, National Cheng Kung Univ. (Taiwan); **Yasuhiro Mizutani**, Osaka Univ. (Japan); **Christian Rembe**, Technische Univ. Clausthal (Germany); **Yukitoshi Otani**, Utsunomiya Univ. (Japan); **Pavel Pavlicek**, Palacký Univ. Olomouc (Czech Republic); **Takamasa Suzuki**, Niigata Univ. (Japan); **Satoru Takahashi**, The Univ. of Tokyo (Japan); **Toshiyuki Takatsuji**, National Institute of Advanced Industrial Science and Technology (Japan); **Toshitaka Wakayama**, Saitama Medical Univ. (Japan); **Wei-Chung Wang**, National Tsing Hua Univ. (Taiwan); **Gao Wei**, Tohoku Univ. (Japan); **Jiangtao Xi**, Univ. of Wollongong (Australia); **Hayato Yoshioka**, Tokyo Institute of Technology (Japan); **Song Zhang**, Purdue Univ. (United States)

Papers on the following and related topics are solicited for this conference:

- 3D profilometry
- polarimetry/ellipsometry
- novel optical testing
- surface inspection methods and applications
- absolute testing for metrology
- application of interferometric techniques
- machine/robot vision methods, architectures and applications
- lighting methods and systems for inspection
- dynamic measurement
- unique optical systems for inspection and measurements
- 2D and 3D machine vision methods and applications
- 3D data acquisition
- freeform testing
- scatterometry
- unconventional microscope for inspection
- super-high accurate measurement for smooth surfaces

- micro- and nano-scale measurement methods
- structured light methods, fringe projection measurement and applications
- phase shifting methods applied to industrial inspection
- mechanic-optics and photonics for metrology and inspection
- optical inspection by optical comb
- super resolution microscope for inspection
- spherical and aspherical measurements
- color metrology of manufactured goods
- on-line and process control measurements
- on-machine tool measurements of shape and finish
- high-resolution and high-speed inspection applications
- novel interferometry.

CONFERENCE CHAIR



**Takeshi Hatsuzawa**

Tokyo Institute of Technology (Japan)

CONFERENCE CO-CHAIRS

**Rainer Tutsch**

Technische Univ. Braunschweig (Germany)

**Toru Yoshizawa**

Tokyo Univ. of Agriculture and Technology (Japan)

**SPIE** STRUCTURED LIGHT

**Submission site opens**

1 October 2019

**Registration opens**

18 December 2019

**Abstracts due**

16 January 2020

Submit your abstract today

<https://opicon.jp/conferences/OPTM>